

L Number	Hits	Search Text	DB	Time stamp
-	18	laser adj thermal adj anneal\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 16:02
-	3922	laser adj anneal\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 16:28
-	23	(laser adj anneal\$3) with ((source and drain) adj region)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 16:04
-	0	(laser adj anneal\$3) with (continous adj puls\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 16:40
-	0	(laser adj anneal\$3) with (mutli\$3 adj puls\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 16:40
-	380	(laser adj anneal\$3) with puls\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 16:30
-	33	((laser adj anneal\$3) with puls\$3) with continuous	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 16:31
-	0	(laser adj anneal\$3) with (continuous adj puls\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 17:04
-	3	(laser adj anneal\$3) with (multi\$3 adj puls\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 16:41
-	0	(laser adj anneal\$3) near (continuous adj puls\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 17:01
-	7	(laser adj anneal\$3) and (continuous adj puls\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 17:07
-	1	(laser adj anneal\$3) with (continuous near puls\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 17:05
-	31584	ion adj implant\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 17:07
-	0	(ion adj implant\$3) and (laser adj anneal\$3 with (continuous or multi) adj pulse)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/07/23 18:27

-	0	(ion adj implant\$3) and (laser adj anneal\$3 with ((continuous or multi) adj pulse))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 17:10
-	1	(ion adj implant\$3) and (laser adj anneal\$3 and ((continuous or multi) adj pulse))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 17:13
-	1486	activat\$3 with (ion adj implant\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 18:39
-	29	(activat\$3 with (ion adj implant\$3)) with (laser adj anneal\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 18:34
-	21	(laser adj substrate) with mov\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 18:44
-	0	((laser adj substrate) with mov\$3) with (activat\$3 with (ion adj implant\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 18:39
-	0	((laser adj substrate) with mov\$3) and (activat\$3 with (ion adj implant\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 18:39
-	0	((laser adj substrate) with mov\$3) with activat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 18:51
-	147	(laser near substrate) with mov\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 18:51
-	11	((laser near substrate) with mov\$3) and ion adj implant\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 18:45
-	2014	(laser with substrate) with mov\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 18:51
-	68	((laser with substrate) with mov\$3) and ion adj implant\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 18:51
-	30	((laser with substrate) with mov\$3) and ion adj implant\$4) and activat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/07/23 18:52